## AMENDMENT

**IN THE CLAIMS:**

Please amend the claims as follows:

1-11. (Canceled)

12. (Previously presented) A film deposition method according to claim 13, wherein

the cleaning of the film deposition system is conducted after a predetermined number of objects to be processed have been processed.

13. (Currently amended) A film deposition method using a film deposition system including a processing vessel capable of being evacuated to make a vacuum therein, a stage placed in the processing vessel and capable of supporting an object to be processed on an upper surface thereof, and a guide ring placed on the stage so as to surround an outer circumference of the object to be processed when mounted on the stage, the guide ring being capable of guiding the object to be processed onto the stage during mounting of the object to be processed onto the stage, wherein a particle generation preventing space ~~having a height between about 0.2 mm to 3 mm~~ is formed between an inner peripheral part of a lower surface of the guide ring and the upper surface of the stage, the method comprising:

determining a height of the particle generation preventing space to be between about 0.2 mm to 3 mm based upon consideration of a cleaning cycle of the film deposition system and a film deposition rate,

mounting an object to be processed onto the stage such that if there is a positional error of the object, the error is corrected by the guide ring;

conducting a film deposition process on the object to be processed by using a $TiCl_4$ gas as a process gas, where upon unnecessary films deposited on wall surfaces defining the particle generation preventing space form peak portions during the conducting of the film deposition process;

removing the object to be processed from on the stage under a condition wherein the guide ring is fitted closely on the upper peripheral part of the stage ~~without changing the particle generation preventing space~~; and

cleaning the film deposition system to remove the unnecessary films and the peak portions thereof, wherein

the unnecessary films peel off the wall surfaces and accumulate in the particle generation preventing space thereby not to disperse as particles into the processing vessel, before the cleaning.

14. (Canceled)

15. (Previously presented) A film deposition method according to claim 13, wherein

the particle generation preventing space has a radial dimension of about 2 mm or more.

16. (Previously presented) A film deposition method according to claim 13, wherein

the particle generation preventing space has a height and a radial dimension, and
a ratio of the radial dimension to the height is 10 or more.